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Amendments to Claims:

Please amend the claims as in the following listing:

What is claimed is:

- 1 1. (currently amended) A method of manufacture of magnetic heads which include CoFe
2 elements using CMP, comprising:
3 A) ~~providing a slurry of Al_2O_3~~ ; providing magnetic heads which include CoFe
4 elements;
5 B) ~~adjusting the concentration of H_2O_2 in said slurry to within a range of 6-12%~~
6 ~~by volume; and providing a slurry including Al_2O_3 and H_2O_2~~ ;
7 C) ~~balancing mechanical polishing action~~; adjusting the concentration of H_2O_2 in
8 said slurry to within a range of 6-12% by volume; and
9 D) balancing mechanical polishing action.
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- 1 2. (original) The method of manufacture of magnetic heads of claim 2, wherein C)
2 includes:
3 adjusting the table speed of a mechanical polisher to within a range of 55-90 rpm.
- 1 3. (original) The method of manufacture of magnetic heads of claim 2, wherein C)
2 includes:
3 adjusting polishing pressure to within a range of 5-7 psi.
- 1 4. (original) The method of manufacture of claim 1, wherein:
2 said slurry of A) includes BTA (1H-benzotriazole).
- 1 5. (original) The method of manufacture of claim 1, wherein:
2 said slurry of A) includes Isothiazolone.
- 1 6. (original) The method of manufacture of claim 1, wherein:
2 the particle size of Al_2O_3 is in the range of 50-500nm.
- 1 7. (original) The method of manufacture of claim 1, wherein:
2 the pH of the slurry is in the range of 4-6.
- 1 8. (withdrawn) A magnetic head which include CoFe elements produced by the process
2 comprising:
3 A) providing a slurry of Al_2O_3 ;
4 B) adjusting the concentration of H_2O_2 in said slurry to within a range of 6-12%
5 by volume; and
6 C) balancing mechanical polishing action.
- 1 9. (withdrawn) The magnetic head of claim 8, wherein C) of the process further
2 comprises:

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3 adjusting the table speed of a mechanical polisher to within a range of 55- 90
4 rpm.

1 10. (withdrawn) The magnetic head of claim 8, wherein C) of the process further
2 comprises:
3 adjusting polishing pressure to within a range of 5-7 psi.

1 11. (withdrawn) The method of manufacture of claim 8, wherein:
2 said slurry of A) includes BTA (1H-benzotriazole).

1 12. (withdrawn) The method of manufacture of claim 8, wherein:
2 said slurry of A) includes Isothiazolone.

1 13. (withdrawn) The method of manufacture of claim 8, wherein:
2 the particle size of Al_2O_3 is in the range of 50-500nm.

1 14. (withdrawn) The method of manufacture of claim 8, wherein:
2 the pH of the slurry is in the range of 4-6.

15. (withdrawn) A slurry for CMP of magnetic head elements including CoFe material,
comprising:
1 Al_2O_3 as an abrasive; and
2 H_2O_2 in concentration within a range of 6-12% by volume.

1 16. (withdrawn) The slurry for CMP of magnetic head elements of claim 15, further
2 comprising:
3 BTA (1H-benzotriazole).

1 17. (withdrawn) The slurry for CMP of magnetic head elements of claim 15, further
2 comprising:
3 Isothiazolone.

1 18. (withdrawn) The slurry for CMP of magnetic head elements of claim 15, wherein:
2 the particle size of Al_2O_3 is in the range of 50-500nm.

1 19. (withdrawn) The slurry for CMP of magnetic head elements of claim 15, wherein:
2 the pH of the slurry is in the range of 4-6.

1 20. (new) A method of manufacture of magnetic heads which include CoFe elements
2 using CMP, comprising:
3 A) providing magnetic heads which include both CoFe elements and Al_2O_3
4 elements;
5 B) providing a slurry including Al_2O_3 and H_2O_2 ;
6 C) adjusting the concentration of H_2O_2 in said slurry to within a range of 8-12%
7 by volume; and

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8 D) balancing mechanical polishing action.
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